

SEMICONDUCTOR FABRICATING APPARATUS

5

ABSTRACT OF THE DISCLOSURE

10 A resonant frequency sensor is disposed in a plasma-  
processing chamber included in a semiconductor  
fabricating apparatus. A change in the resonant  
frequency caused by etching, sputtering or deposition is  
sensed in order to detect the timing of performing the  
maintenance of the processing chamber. If data  
representing the relationship between an amount of  
15 etching or deposition occurring at a predetermined  
position in the processing chamber and occurrence of an  
abnormality is produced in advance, an optimal  
maintenance timing can be determined.